

## F. Silicon and Group-IV Devices and Integration Technology 분과

2017년 2월 15일 (수), 10:10-11:40  
Room E (루비, 2층)

### [WE2-F] Advanced CMOS Materials

좌장: 안동환(국민대학교), 전인상(한국알박)

<b>WE2-F-1</b> 10:10-10:25	<b>Metal/Al<sub>2</sub>O<sub>3</sub>/GeO<sub>2</sub>/Ge 구조의 열처리에 따른 유효 일함수에 대한 연구</b> Tae In Lee, Yujin Seo, Jungmin Moon, Hyun Jun Ahn, Hyun-Young Yu, Wan Sik Hwang, and Byung Jin Cho <i>School of Electrical Engineering, KAIST</i>
<b>WE2-F-2</b> 10:25-10:40	<b>V<sub>TH</sub> Modulation of HfO<sub>2</sub>-MOSFETs with ALD TiN Using TiCl<sub>4</sub> and NH<sub>3</sub></b> Younjin Kim <sup>1</sup> , Donghwan Lim <sup>1</sup> , Myeong Gyoon Chae <sup>1</sup> , Dongkyun Kang <sup>2</sup> , Jaesang Lee <sup>2</sup> , Hojin Cho <sup>2</sup> , Sunggon Jin <sup>2</sup> , Euseong Hwang <sup>2</sup> , and Changhwan Choi <sup>1</sup> <i><sup>1</sup>Division of Materials Science and Engineering, Hanyang University, <sup>2</sup>SK Hynix Inc.</i>
<b>WE2-F-3</b> 10:40-10:55	<b>Metal-Interlayer-Semiconductor Structure Using Al-Doped ZnO for Non-Alloyed Ohmic Contacts on Silicon</b> Seung-Hwan Kim <sup>1</sup> and Hyun-Yong Yu <sup>1</sup> <i><sup>1</sup>School of Electrical Engineering, Korea University</i>
<b>WE2-F-4</b> 10:55-11:10	<b>An Analysis of Carrier Trapping at Grain Boundary of Polysilicon</b> Taejin Jang, Myung-Hyun Baek, Hyungjin Kim, and Byung-Gook Park <i>Department of Electrical Engineering, Seoul National University</i>
<b>WE2-F-5</b> 11:10-11:25	<b>Study on Material Properties of Tensile-Strained Ge and Sn-Incorporated Ge through First-Principle Simulation for Advanced Si CMOS Technology</b> Yongbeom Cho <sup>1</sup> and Seongjae Cho <sup>1,2</sup> <i><sup>1</sup>Graduate School of IT Convergence Engineering, Gachon University, <sup>2</sup>Department of Electronics Engineering, Gachon University</i>
<b>WE2-F-6</b> 11:25-11:40	<b>Impact of Equivalent Oxide Thickness on Threshold Voltage Variation Induced by Work-Function Variation in FinFET</b> Youngtaek Lee, Gihun Choe, Hyunjae Lee, and Changhwan Shin <i>Department of Electrical and Computer Engineering, University of Seoul</i>